

Form PTO-1449UC95 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. M122-1398		SERIAL NO. 09/536,037	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Walmin (Michael) Li et al.	
FILING DATE March 27, 2000				GROUP 2822	

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 PATENT & TRADEMARK OFFICE

U.S. PATENT DOCUMENTS							
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA 6,318,122	02/03	Chan et al.				
	AB 6,492,688	12/02	Ug (ILO)				
	AC 6,373,114	04/02	Jeng et al.				
	AD 6,001,747	12/14/1999	Annapragada				
	AE 2001/0019668	9/01	Gonzalez et al.				
	AF 2001/0003064	6/01	Ohto				
	AG 2003/0013311	1/03	Chang et al.				
	AH						
	AI						
	AJ						
	AK						
	AL						

FOREIGN PATENT DOCUMENTS								
	Document Number	Date	Country	Class	Subclass	Translation		
						Yes	No	
	AM							
	AN							
	AO							
	AP							
	AO							

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)			
	AR		"Silicon Processing for The VLSI Era"; Wolf, Stanley, Ph.D., Lattice Press 1986
	AS		
	AT		

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EXAMINER	DATE CONSIDERED
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Form PTO-1449

U.S. DEPARTMENT OF COMMERCE
PATENT AND TRADEMARK OFFICEATTY. DCKL NO.
M122-1398SERIAL NO.
09/538,037LIST OF ART CITED BY APPLICANT
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Weimin (Michael) Li et al.FILING DATE
March 27, 2000GROUP
2822

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		Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	AA	4,474,975	10-2-1984	Clemons et al.			
	AB	5,962,581	10-5-1999	Hayase et al.			
	AC	4,805,683	2-21-1989	Magdo et al.			
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	AV	5,674,358	10-7-1997	Nagayama			
	AW	5,731,242	3-24-1998	Parat et al.			
	AX	5,741,721	4-21-1998	Stevens			

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Sheet 1 of 1

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LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Wolfe (Michael) U et al.			
				FILING DATE March 17, 2003		GROUP 1212	
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*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date if Appropriate
	AA	6,001,747	12/14/1999	ANAPRAGADA	438	790	
	AB						
	AC						
	AD						
	AE						
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	AG						
	AH						
	AI						
	AJ						
	AK						
	AL						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes No
	AM						
	AN						
	AO						
	AP						
	AQ						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
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